DI-Solver[™] NH₃

Dissolved Ammonia Delivery System



The MKS DI-Solver™ NH₃ is a compact, stand-alone system designed to provide dissolved ammonia water for use in rinsing processes in the semiconductor industry. The system is specifically designed to provide optimal cleaning capability at a given conductivity. The alkaline chemistry of dissolved ammonia provides ESD protection during rinsing, particle lift-off, and residual particle removal. It also prevents

corrosion of metal interfaces, which is a common problem in semiconductor manufacturing. The system uses closed-loop control to keep conductivity and pressure stable under changing flow conditions. It also monitors and adjusts the NH₄OH concentration to deliver the desired level of dissolved ammonia.

Product Features

- Precise conductivity control in range from 5 to 121 µS/cm
- Flow rates up to 40 lpm
- <5% conductivity stability
- Proprietary gas dosage through mass flow control system
- Perfectly suited for high purity applications

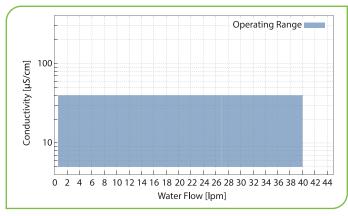


Key Benefits

- Best dynamic conductivity control and accuracy at point of use from proprietary control of gas
- Increases yields by inhibiting Electrostatic Discharge
- Improves interconnect reliability and yield by preventing metal surface and post CMP clean corrosion
- Cost effective water, power and chemical consumption reduces operating costs

MKS' DI-Solver NH₃ leverages the established and proven architecture of LIQUOZON® Ozonated Water Delivery System, integrating high purity standard materials and safety features in a rugged system to meet the demands of advanced technology manufacturing.

The below figures show the possible performance ranges of different configurations that provide a conductivity range of 5 to 40 μ S/cm at 0.5 to 40 lpm (Figure 1), or 5-121 μ S/cm at 0.5 to 32 lpm (Figure 2).



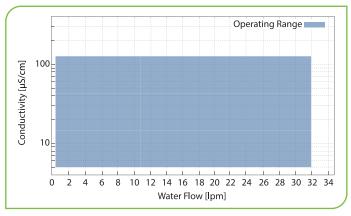
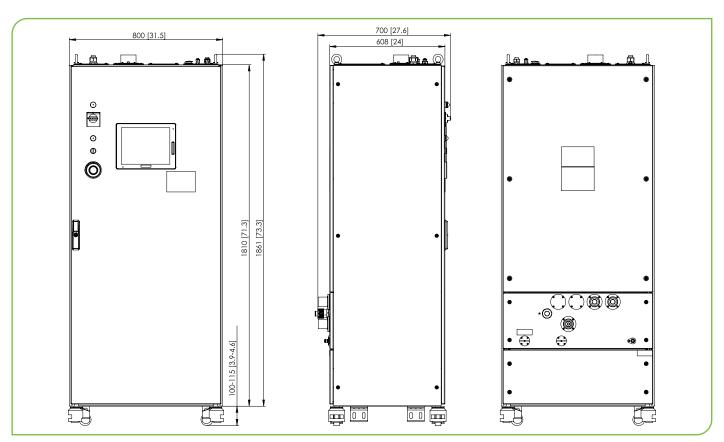


Figure 1 - Conductivity range of 5 to 40 μS/cm at 0.5 to 40 lpm Figure 2 - Conductivity range of 5-121 μS/cm at 0.5 to 32 lpm Specified achievable dissolved ozone concentration in UPW for a system pressure of 2.5 bar₉, a cooling water temperature and UPW temperature of 20°C.

Dimensional Drawing



Note: Unless otherwise specified, dimensions are nominal values in millimeters (inches referenced).



Specifications

System Specifications	
Ammonia Water (DI-NH ₃)	Configurable 1.0-3.0 bar _g (3.7 bar _g with outlet pump)
Plumbing Materials	
Liquid Wetted Surfaces	PFA, PTFE, quartz glass
Gas Wetted Surfaces	316L stainless steel, PFA, PTFE
Communication	Binary in/out, RS232/RS485, analog 4 – 20 mA in/out, USB
Cabinet, Dimensions (H x W x D)	 Coated steel, approx. 1810 mm x 800 mm x 610 mm (71.2" x 31.5" x 24.1")
	Overall height: approx. 2000 mm (79")
Weight	Approx. 290-300 kg, depending on configuration
Compliance	CE, SEMI S2, SEMI F47, NRTL
Facility Requirements	
N ₂	 ≥Grade 4 (purity ≥99.99%), dew point <-40°C
Inlet Pressure Surfaces	 4.5 - 7.6 bar_g (65 - 110 psig), at least higher 3 bar than system pressure
Standard Flow Rate	• ≤10 slm, according to SEMI E12 (0°C / 1.01325 bar)
Ammonia (NH₃)	• ≥Grade 4.5 (purity ≥99.995%)
Inlet Pressure	• 3.0 – 5.0 bar _g (44 - 73 psig)
Standard Flow Rate	 ≤2.0 slm, according to SEMI E12 (0°C / 1.01325 bar)
Ultra-Pure Water (UPW)	 <0.1 ppb metals, <10 particles/ml of 0.1µm size, free of organics
UPW IN Pressure	• 1.3 - 4 bar _g (14.5 - 73 psig), at least 1.3 bar higher than system pressure
Temperature	• 20 – 25°C (59 – 77°F), rated 20°C (68°F)
Clean Dry Air (CDA)	Filtration, free of oils and particles
Pressure	• 6.0 – 8, 3 bar _g (87 – 120 psig)
Flow Rate	• ≤15 slm, typically 10.0 slm according to SEMI E12 (0°C / 1.01325 bar)
Exhaust	
Cabinet Underpressure	• >8mm (0.32") water column
Standard Flow Rate	 >70m³/h, according to SEMI S6 (21.1°C / 1.01325 bar)
Power	3/PE~, 200 - 208 V ±10 %, 50/60 Hz, collective 1050 W



Ordering Information

Please contact your local MKS sales office for price and availability information.

